

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

RENE MONSHOUWER ET AL

NL 000770

Serial No.

Filed: CONCURRENTLY

METHOD OF MEASURING ALIGNMENT OF A SUBSTRATE WITH RESPECT TO
A REFERENCE ALIGNMENT MARK

Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Prior to calculation of the filing fee and examination,
please amend the above-identified application as follows:

IN THE SPECIFICATION

Page 21, in the paragraph beginning on line 9,

With an off-axis alignment-measuring device, for
example that of Fig. 8, not only the position of a substrate
but also the position of the substrate holder or substrate
table can be measured. To this end, the holder or table is
also provided with an alignment mark similar to the global
substrate alignment mark. If the position of the substrate
holder with respect to the reference in the alignment-
measuring device has been determined, the position of the
substrate mark with respect to the substrate holder mark will
be known. To be able to determine the mutual position of the
mask pattern and the substrate, a further measurement is
necessary, namely that of the position of the mask pattern
with respect to the substrate holder or table. For this

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